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Front Matter: Volume 11175

, "Front Matter: Volume 11175," Proc. SPIE 11175, Optifab 2019, 1117501 (15 November 2019); doi: 10.1117/12.2559224

SPIE.

Event: SPIE Optifab, 2019, Rochester, New York, United States

PROCEEDINGS OF SPIE

Optifab 2019

Blair L. Unger
Jessica DeGroote Nelson
Editors

14–17 October 2019
Rochester, New York, United States

Sponsored by
SPIE

Cosponsored by
The American Precision Optics Manufacturers Association (United States)

Published by
SPIE

Volume 11175

Proceedings of SPIE 0277-786X, V. 11175

SPIE is an international society advancing an interdisciplinary approach to the science and application of light.

Optifab 2019, edited by Blair L. Unger, Jessica DeGroote Nelson, Proc. of SPIE Vol. 11175,
1117501 · © 2019 SPIE · CCC code: 0277-786X/19/\$21 · doi: 10.1117/12.2559224

Proc. of SPIE Vol. 11175 1117501-1

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Author(s), "Title of Paper," in *Optifab 2019*, edited by Blair L. Unger, Jessica DeGroote Nelson, Proceedings of SPIE Vol. 11175 (SPIE, Bellingham, WA, 2019) Seven-digit Article CID Number.

ISSN: 0277-786X

ISSN: 1996-756X (electronic)

ISBN: 9781510630635

ISBN: 9781510630642 (electronic)

Published by

SPIE

P.O. Box 10, Bellingham, Washington 98227-0010 USA

Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445

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